# Kinetics simulation of TiB<sub>2</sub> layers on the titanium alloy (Ti6Al4V) obtained by liquid boriding process

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#### Abstract

In this study, we conducted a kinetics simulation of TiB<sub>2</sub> layers obtained by the boriding process in the temperature range of 1123–1323 K. To investigate the influence of different boriding parameters, we developed a mathematical model based on Fick's law and the mass balance equation. This model allows us to estimate the boron concentration in the TiB<sub>2</sub> phase, the boride layer thickness, and the mass gain. To validate the simulation results, we compared them with our experimental data on liquid boriding with a salt bath consisting of 70 % Borax (Na2B4O7) and 30 % Silicon carbide (SiC) applied to the titanium alloy (Ti6Al4V). The comparison confirmed the validity of our model, assuring the accuracy of our simulation results.

Key words: liquid boriding, titanium borides, kinetics, diffusion model, simulation

#### 1. Introduction

Titanium and its alloys are generally utilized in aviation, petrochemical, car, and biomedical applications owing to their properties, for example, their high strength-to-weight ratio (even at high temperatures), their outstanding biocompatibility, and their great resistance against corrosion and oxidation [1, 2]. In any case, low wear resistance associated with a low hardness limits its utilization, especially in tribological applications, because of the inherent nature of titanium [3, 4]. In this way, a few surface modification methods, for example, nitriding [5], oxidizing [6], and carburizing [7] on titanium surfaces, are considered the adequate methods to improve surface hardness and strength wear of titanium and its alloys.

The boriding technique is frequently utilized for titanium and its alloys to obtain a hard boride layer by thermodiffusion of boron atoms into the metallic substrate [8]. This hard boride layer is produced in the temperature range of 973–1373 K by different techniques, including laser boriding [9], plasma-assisted boriding [10], pack boriding [11], boriding in molten salts [12].

The modeling of boriding kinetics by different approaches is of great importance in controlling the boriding parameters such as the treatment time, the temperature, and the boron concentration [13]. For instance, Campos et al. [14] have used a mathematical model based on Fick's law to estimate the boron diffusion coefficients in the Fe<sub>2</sub>B layer formed on Armco iron substrate by the powder-pack boriding. In another model, Keddam et al. [15] proposed a kinetic model based on the integral method to estimate the boron diffusion coefficients in the Fe<sub>2</sub>B layers on AISI P20 steel. Kulka et al. [16] have simulated the growth kinetics of FeB and Fe<sub>2</sub>B layers on Armco iron substrate produced by the gas boriding in the H<sub>2</sub>-BCl<sub>3</sub> atmosphere.

Mebarek et al. [17] have investigated the kinetics of

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Fig. 1. Schematic representation of the boron concentration profile along the  $TiB_2$  layer.

the formation of Fe<sub>2</sub>B layers on AISI 316 steel formed by liquid boriding in a salt bath composed of (70 wt.% Borax and 30 wt.% Silicon carbide) between 1073 K and 1373 K. In their model, the value of activation energy for boron diffusion was estimated as equal to  $174.6 \text{ kJ mol}^{-1}$  for AISI 316 stainless steel. In another study, Mebareket et al. [18, 19] employed the artificial intelligence technique for simulating the boriding kinetics.

The modeling of the growth kinetics of titanium borides was already detailed by Keddam et al. [20]; the developed model is based on the mass balance equation. This model is used to simulate the layers' thicknesses of TiB<sub>2</sub> and TiB, in which the titanium boride layers were produced by plasma paste boriding on Ti6Al4V at 973–1073 K.

In this paper, the boriding kinetics of Ti6Al4V alloy was investigated. The experimental data obtained by liquid boriding on Ti6Al4V alloy were used [21]. A single-phase layer (TiB<sub>2</sub>) at the surface of Ti6Al4V alloy was formed during this process in the temperature range 1123-1273 K.

A mathematical model was suggested to predict the  $\text{TiB}_2$  layer thickness, the parabolic growth constant, the boron concentration profile inside the  $\text{TiB}_2$ phase, and the mass gain as a function of boriding parameters (see Fig. 1).

### 2. Simulation model

To simulate the diffusion of boron into the Ti6Al4V alloy, we used the second Fick's law given by Eq. (1):

$$\frac{\partial C_i(x,t)}{\partial t} = D_i \frac{\partial^2 C_i(x,t)}{\partial x^2} \tag{1}$$

with

$$D_i = D_i^0 \exp\left(-\frac{Q}{RT}\right),\tag{2}$$

where  $D_i^0$  is a pre-exponential factor,  $Q_i$  represents the activation energy per mole, R is the universal gas constant ( $R = 8.314 \text{ J} \text{ mol}^{-1} \text{ K}^{-1}$ ), and T is the temperature.

The general solution of Eq. (1) for each phase i is given by:

$$C_i(x,t) = A_i + B_i \operatorname{erf}\left(\frac{x}{2\sqrt{D_i t}}\right).$$
(3)

The solution of Eq. (3) simulates the boron concentration in the TiB<sub>2</sub> phase, with  $C_{\rm up}$  and  $C_{\rm low}$  as the upper and lower limits of boron concentrations in the TiB<sub>2</sub> phase. The term  $C_{\rm ads}$  represents the adsorbed concentration of boron.

This study considers that the boron concentration is linear through the  $TiB_2$  layer.

To calculate the boron concentration inside the  $TiB_2$  phase, we consider the following conditions:

for 
$$t = t$$
 and  $x = 0$ ,  $C(t, 0) = C_{up}$ , if  $t > 0$  and  $x = \lambda$ ,  
 $C(t, x) = C_{low}$ .

From this condition, we estimate the boron concentration profile in the TiB<sub>2</sub> phase, where  $\lambda$  is the boride layer thickness of TiB<sub>2</sub>.

We use the mass balance equation to calculate the  $TiB_2$  layer thickness based on the expression of mass conservation at the  $TiB_2$ /substrate interface. The displacement of the interface is described by Eq. (4):

$$\left. a \frac{\mathrm{d}x}{\mathrm{d}t} \right|_{x=\lambda} = -D_{\mathrm{TiB}_2} \left. \frac{\partial C_{\mathrm{B}}^{\mathrm{TiB}_2}(x,t)}{\partial x} \right|_{x=\lambda} \tag{4}$$

with

$$a = \left[\frac{(C_{\rm up} - C_{\rm low})}{2} + (C_{\rm low} - C_0)\right]$$

where  $C_0$  ( $C_0 = 0$ ) is the boron concentration in the matrix, D is the boron diffusion coefficient in the TiB<sub>2</sub> phase,  $C_{\rm up}$  is the upper limit of boron in the TiB<sub>2</sub> phase, while  $C_{\rm low}$  denotes the lower value of boron in the TiB<sub>2</sub> layer.

In this study, we consider that the time dependence of  $TiB_2$  layer thickness is expressed by a parabolic law given by Eq. (5):

$$\lambda = k\sqrt{t},\tag{5}$$

where k represents the growth rate constant.

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Al	V	Fe	С	Η	Ν	Ο	Ti	
6.13	3.98	0.15	0.04	0.001	0.011	0.14	Bal	

Table 1. Chemical composition of Ti6Al4V alloy (in



Fig. 2. Boriding device [21].

With the use of previous equations and after the rearrangement of Eq. (4), the expression of boron diffusion coefficients in the  $TiB_2$  layer can be derived as follows:

$$D_{\rm TiB_2} = \frac{k^2}{4} \left( \frac{C_{\rm up} + C_{\rm low}}{C_{\rm up} - C_{\rm low}} \right). \tag{6}$$

The values of upper and lower boron contents in TiB<sub>2</sub> are taken from reference [20], with  $C_{\rm up} = 31.10 \text{ wt.\%}$  and  $C_{\rm low} = 30.10 \text{ wt.\%}$ .

#### 3. Experimental procedure

In this experimental study, the Ti6Al4V alloy has been used as a substrate for boriding in a liquid medium [21]. Table 1 shows the chemical composition of this material.

The samples to be borided had a cylindrical shape with a diameter of 10 mm and a length of 12 mm. To avoid any oxidation which can disturb the kinetics of boriding, the surfaces to be borided were polished with silicon carbide paper progressively up to a particle size of 1200 grains cm<sup>-2</sup> just before boriding treatment. Then, they were washed with distilled water, degreased with ultrasound in acetone, and rinsed with alcohol.



Fig. 3. Optical micrograph of a cross-section of the boride layer obtained at the surface of Ti6Al4V alloy at 1273 K for 8 h.



Fig. 4. Observation by scanning electron microscopy of the boride layer at 1273 K for 8 h.

The samples were borided in the open air in a liquid environment by immersion in an electric salt bath oven (Fig. 2). Liquid boriding was carried out in molten salts containing 70 % by weight of Na<sub>2</sub>B<sub>4</sub>O<sub>7</sub> and 30 % by weight of SiC. Three boriding temperatures, 1123, 1223, and 1273 K, were used with 2, 4, 6, and 8 h treatment times. After the boriding treatment, all samples were removed from the furnace, air-cooled to ambient temperature, and cleaned from any residue adhering to the surface (see Figs. 3, 4).

## 4. Results and discussion

# 4.1. Evaluation of the activation energy for boron diffusion

To assess the values of boron diffusion coefficients in the  $TiB_2$  layers, the values of parabolic growth con-

Temperature (K)	Experimental parabolic growth constants ( $\mu m s^{-0.5}$ ) [21]	$D_{\rm TiB_2} \ ({\rm m^2 \ s^{-1}})$ with Eq. (6)
1123 1223 1273	0.0918 0.2283 0.2825	$1.29  imes 10^{-13} \ 7.97  imes 10^{-13} \ 12.2  imes 10^{-13}$

Table 2. Calculated values of boron diffusion coefficients in  $TiB_2$  with the corresponding experimental parabolic growth constants

Table 3. Comparison of boron activation energies for titanium alloys by different methods

Materials	Boriding method	Activation energy $(kJ mol^{-1})$	Ref.
Cp-Ti	Molten-salt	$225.617 (TiB_2)$	[22]
Cp-Ti	CRTD-boriding	$189.9(\mathrm{TiB}_2)$	[23]
TB2 alloy	Pack boriding	158.056	[24]
Ti6Al4V	Ti6Al4V/Sigma fiber composites	$187 (TiB_2) 190 (TiB)$	[27]
Ti6Al4V	Pack boriding	$231.177 ((TiB_2))$	[26]
Ti6Al4V	Plasma paste	$136 (TiB_2) 63 (TiB)$	[20]
Ti6Al4V	Superplastic boronizing	226.17 (TiB <sub>2</sub> )	[25]
Ti6Al4V	Liquid boriding	183.14 (TiB <sub>2</sub> )	Present study



Fig. 5. Temperature dependence of calculated boron diffusion coefficients in TiB<sub>2</sub>.

stants derived from the plot of layer thickness against the square root of time are needed.

The experimental parabolic growth constants were obtained based on the kinetic results of Fig. 5 of reference [21]. The estimated values of boron diffusivities for the TiB<sub>2</sub> layer with Eq. (6) are listed in Table 2 for an upper boron content of 31.10 wt.% in TiB<sub>2</sub>.

To get the value of boron activation energy in  $TiB_2$ , the values of boron diffusion coefficients in the  $TiB_2$  layers were fitted with the Arrhenius equation, as shown in Fig. 5.

From Fig. 5, the value of activation energy for

boron diffusion in Ti6Al4V alloy was estimated as  $183.14 \text{ kJ} \text{ mol}^{-1}$ . The diffusion coefficient of boron in TiB<sub>2</sub> was fitted with the Arrhenius equation in the temperature range 1123-1273 K. The temperature dependence of the boron diffusion coefficient in TiB<sub>2</sub> in the temperature range 1123-1273 K was given by Eq. (7):

$$D_{\text{TiB}_2} = 4.48 \times 10^{-5} \exp\left(-\frac{183.14 \text{ kJ mol}^{-1}}{RT}\right).$$
 (7)

Table 3 lists the values of the boron activation energies for titanium alloys by different methods and for different materials. From Table 3, the values of the activation energies obtained are dependent on the boriding method (liquid, solid, and gas medium).

Generally, the activation energies depend on the chemical composition of the treated material, the boriding method, and the temperature treatment.

It is seen that the obtained value of boron activation energy in Ti6Al4V alloy is consistent with the results displayed in Table 3.

From Table 3, we can observe different values of the activation energy. Variations in the boriding method and diffusion model employed in different studies can lead to observed differences in activation energies. Different boriding methods can result in variations in the microstructure and composition of the boride layer. The specific conditions, such as the temperature, the time, the boron source, and the atmosphere composition, can influence the diffusion kinetics and the resulting layer characteristics. Generally, to calculate the activation energy, we use many diffusion models to make assumptions about factors like concentration

Growth rate constants $(\mu m s^{-1/2})$				
Temperature (K)	Calculated $k \ (\mu m \ s^{-1/2})$	Experimental $k \; (\mu \mathrm{m \; s}^{-1/2}) \; [21]$		
1123	0.0940	0.0918		
1223	0.2099	0.2283		
1273	0.2990	0.2825		

Table 4. Calculated and experimental growth rate constants k

Table 5. Time dependence of the  $TiB_2$  boride layer thickness for increasing temperatures (the results in bold are the simulated values)

Temperature (K) Time (h)	1123	1223	1273	
2	7.71/ <b>7.97</b>	15.21/ <b>17.81</b>	19.71/ <b>25.37</b>	
4	10.01/11.28	26.57/ <b>25.18</b>	30.85/ <b>35.88</b>	
6	13.07/ <b>13.81</b>	34.9/ <b>30.84</b>	42.0/43.94	
8	16.7/15.95	40.8/35.62	51.85/ <b>50.74</b>	



Fig. 6. Evolution of the growth rate constant vs. temperature.

gradients, diffusion paths, and diffusivity. These factors can directly impact the calculated activation energy. Fan et al. [27] studied the reaction kinetics between the TiB, coating, and Ti matrix for the diffusion coefficient calculation. The diffusion mechanisms for B atoms in TiB and TiB<sub>2</sub> have been identified in this study vacancy diffusion; the authors note that the activation energy for boron diffusion in TiB is notably lower along the  $(0\ 1\ 0)$  TiB direction, which can be regarded as a nearly one-dimensional pathway. Conversely, in TiB<sub>2</sub>, the diffusion path predominantly follows the (100) TiB<sub>2</sub> directions, forming a two-dimensional network.

Therefore, if different studies employ different boriding methods or diffusion models, variations in the observed activation energies would likely arise.

#### 4.2. Kinetic studies

Using the model of the growth kinetics of boride layers mentioned previously, we have implemented a simulation code to calculate the  $TiB_2$  layer thickness and predict the boron concentration profile inside the  $TiB_2$  phase.

The diffusion and thermodynamic data used in this model are the diffusivity of boron in TiB<sub>2</sub> calculated with Eq. (7); the upper limit of boron content in TiB<sub>2</sub> represents the boron concentration at the surface with the value of 31.10 wt.%, the lower limit of boron content in TiB<sub>2</sub> (= 30.10 wt.%).

The comparison between the growth rate constants obtained by simulation and experimental data is shown in Table 4.

We notice a good agreement between our experimental data and the calculated data at 1123, 1223, and 1273 K (the boron concentration at the surface is  $C_{\rm up} = 31.10 \text{ wt.}\% \text{ B}$ ).

There is a good agreement between the simulated growth rate constants and experimental values of parabolic growth constants. The growth kinetics of the boride layer increases with the temperature.

Table 5 compares the experimental values of  $\text{TiB}_2$  layer thickness and the simulated thicknesses for an upper boron content of 31.10 wt.% in  $\text{TiB}_2$ . It is seen that the experimental data [21] are in line with the simulated results.



Fig. 7. Variation of simulated growth rate constant as a function of upper boron content in TiB<sub>2</sub>.

The simulated values of TiB<sub>2</sub> layer thickness indicated in bold in Table 5 are between 8.76 and 57.9  $\mu$ m. It is also noted that the TiB<sub>2</sub> layer thickness increases with the temperature rise for a given treatment time.

Generally, the boriding of the titanium leads to the formation of  $\text{TiB}_2$  and TiB instantly; the TiB layer is very thin compared to the  $\text{TiB}_2$  in the case of bilayer configuration, we will obtain the bilayer configuration with an important layer thickness of TiB if we increase the boron concentration in the surface.

In practice, it is difficult to experimentally measure the boride layer thickness from the optical microscope investigation; this difficulty arises from the microstructural nature of the interface (boride layer/substrate).

Figure 7 describes the variation of the simulated growth rate constant as a function of the upper boron concentration in TiB<sub>2</sub> at the material surface. This figure evaluates the parabolic growth rate constant for the concentration between  $C_{\text{low}}$  and the boron concentration of 43.10 wt.%.

From Fig. 7, we note that the growth rate constant increases with the rise of upper boron concentration in  $TiB_2$ . This leads to an increase in the boride layer thickness.

The boron concentration at the surface plays an important role in the kinetics of the boriding process.

The surface boron concentration is a key parameter responsible for accelerating or optimizing the boriding process and has to be chosen based on different criteria (the boride layer's thickness and the duration of the process). With increasing temperature, the diffusion process proceeds quickly through the borided layer.

In Fig. 8, the calculated boron concentration pro-



Fig. 8. Calculated boron concentration profiles along the  $TiB_2$  layer for a treatment time of 4 h at increasing temperatures with an upper boron content of 43.10 wt.% in  $TiB_2$ .

files along the TiB<sub>2</sub> layer are plotted for 4 h at increasing temperatures using Eq. (3). The boron content in the TiB<sub>2</sub> phase changes with the boriding temperature. At high temperatures, the boron content rapidly attains a limit value of the boron concentration in the TiB<sub>2</sub> phase required for its development and growth.

The mass gain per unit area is evaluated using Eq. (8). The calculation is based on the assumption that the TiB<sub>2</sub> layer is formed instantly at t = 0 and immediately covers the surface:

$$G(t) = 2\rho \frac{(C_{\rm up} - C_{\rm low})}{\operatorname{erf}\left(k/2\sqrt{D_{\rm TiB_2}}\right)} \sqrt{\frac{D_{\rm TiB_2}}{\pi}}t, \qquad (8)$$

where G(t) represents the mass gain  $(\text{g cm}^{-2})$  and  $\rho$  is the titanium density  $(= 4.506 \text{ g cm}^{-3})$ .

Figure 9 shows the time dependence of mass gain associated with forming the TiB<sub>2</sub> layer at the surface of the Ti6Al4V alloy for increasing temperatures with an upper boron content of 31.10 wt.% in TiB<sub>2</sub>. Figure 9 shows that the mass gain increases with the boriding temperature.

#### 5. Conclusions

In this study, a mathematical diffusion model is applied to simulate the growth kinetics of the  $TiB_2$  layer formed on Ti6Al4V alloy by liquid boriding in the temperature range 1123–1273 K. By analyzing the kinetics data, the value of activation energy for boron diffusion



Fig. 9. Time dependence of mass gain recorded at the surface of Ti6Al4V alloy for increasing temperatures.

in Ti6Al4V alloys was estimated as  $183.14 \text{ kJ mol}^{-1}$ . This value of energy was compared to the literature data.

Our simulation model can predict the boron concentration profile inside the  $TiB_2$  phase and its layer thickness. With this simulation, we can estimate the influence of different parameters such as the temperature, the boriding duration, and the upper boron concentration in  $TiB_2$  at the material surface on the boriding kinetics of Ti6Al4V alloy. Finally, the simulation results were in good agreement with the experimental data.

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